



PTO/SB/21 (02-04)

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**TRANSMITTAL
FORM**

(to be used for all correspondence after initial filing)

TRANSMITTAL FORM (to be used for all correspondence after initial filing)	Application Number	10/614,716
	Filing Date	07/07/2003
	First Named Inventor	Sreenivasan et al.
	Art Unit	1732
	Examiner Name	Unassigned
Total Number of Pages in This Submission	Attorney Docket Number	P90/MII-51-33V50

ENCLOSURES (Check all that apply)

<input type="checkbox"/> Fee Transmittal Form	<input type="checkbox"/> Drawing(s)	<input type="checkbox"/> After Allowance communication to Technology Center (TC)
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<input type="checkbox"/> After Final	<input type="checkbox"/> Petition to Convert to a Provisional Application	<input type="checkbox"/> Proprietary Information
<input type="checkbox"/> Affidavits/declaration(s)	<input type="checkbox"/> Power of Attorney, Revocation Change of Correspondence Address	<input type="checkbox"/> Status Letter
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<input checked="" type="checkbox"/> Information Disclosure Statement	<input type="checkbox"/> CD, Number of CD(s) _____	Forty-two (42) References
<input type="checkbox"/> Certified Copy of Priority Document(s)	Remarks	Return Receipt Postcard to K. C. Brooks
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SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT

Firm or Individual name	Law Office of Kenneth C. Brooks
Signature	<i>Kenneth C. Brooks</i>
Date	3/11/04

CERTIFICATE OF TRANSMISSION/MAILING

I hereby certify that this correspondence is being facsimile transmitted to the USPTO or deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on the date shown below.

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This collection of information is required by 37 CFR 1.5. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Sreenivasan et al.

PATENT APPLICATION

Serial No.: 10/614,716

Group Art Unit: 1732

Filing Date: July 7, 2003

Examiner: Unassigned

For: A CONFORMING TEMPLATE FOR PATTERNING LIQUIDS DISPOSED
ON SUBSTRATES

INFORMATION DISCLOSURE STATEMENT

Commissioner
for Patents
Alexandria, VA 22313

Sir:

The following information is submitted in compliance
with Applicants' duty of disclosure under 37 C.F.R. § 1.56.

Form PTO-1449 and a copy of each reference recited below
accompanies this document. It is respectfully requested that
the cited information be expressly considered during the
prosecution of this application, and the references be made
of record therein and appear among the "references cited" on
any patent to issue therefrom.

ISSUED PATENTS

<u>Patent Number</u>	<u>Inventor</u>	<u>Grant Date</u>
4,724,222	Feldman	02/09/1988
4,731,155	Napoli et al.	03/15/1988
5,425,848	Haisma et al.	06/20/1995
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6,334,960	Willson et al.	01/01/2002
6,518,168	Clem et al.	02/11/2003

PENDING PATENT APPLICATIONS

<u>Serial Number</u>	<u>Inventor</u>	<u>Filing Date</u>
09/698,317	Choi et al.	10/27/2000
09/907,512	Sreenivasan et al.	07/16/2001
09/908,455	Choi et al.	07/17/2001
09/920,341	Choi et al.	08/01/2001
09/976,681	Bailey et al.	10/12/2001
10/136,188	Voisin	05/01/2002p
10/194,414	Sreenivasan et al.	07/11/2002
10/194,991	Sreenivasan et al.	07/11/2002
10/293,224	Choi et al.	11/13/2002
10/293,919	Voisin	11/13/2002
10/316,963	Choi et al.	12/11/2002
10/735,110	Nimmakayala et al.	12/12/2003

FOREIGN PATENT DOCUMENTS

<u>Document Number</u>	<u>Inventor</u>	<u>Pub. Date</u>
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JP 1-196749	Matsumoto et al.	08/08/1989
WO 01/69317	Montelius et al.	09/20/2001
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WO 01/90816	Heidari	11/29/2001

NON-PATENT DOCUMENTS

Krug, Herbert et al. "Fine Patterning of Thin Sol-Gel Films,"
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Krauss, et al. "Fabrication of Nanodevices Using Sub-25nm
Imprint Lithography," Appl. Phys. Lett., 67(21), 3114-
3116, 1995.

Chou et al. "Imprint of Sub-25 nm Vias and Trenches in
Polymers," Applied Physics Letters, 67(21), pp. 3114-3116,
1995.

Chou et al. "Imprint Lithography with 25-Nanometer
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- Haisma, J. et al. "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication," Journal of Vacuum Science and Technology, 1996, 14, 4124-4128.
- Chou et al. "Imprint Lithography with Sub-10 nm Feature Size and High Throughput", Microelectronic Engineering 35, 1997, 237-240.
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- Scheer, H.C. et al. "Problems of Nanoimprinting Technique for Nanometer Scale Pattern Definition," Journal of Vacuum Science and Technology, 1998, 16, 3917-3921.
- Colburn, M. et al. "Step and Flash Imprint Lithography: New Approach to High-Resolution Patterning," Proc. of SPIE, 1999, 3676, 379-389.
- Chou, Stephen et al. "Lithographically-induced Self Assembly of Periodic Micropillar Arrays," Journal of Vacuum Science and Technology, 1999, 17, 3197-3202.
- Ruchhoeft, P. et al. "Patterning Curved Surfaces: Template Generation by Ion Beam Proximity Lithography and Relief Transfer by Step and Flash Imprint Lithography," Journal of Vacuum Science and Technology, 1999, 17, 2965-2982.
- Choi, B.J. et al. "Design of Orientation Stages for Step and Flash Imprint Lithography," Precision Engineering, 2001, 25, 192-199.

Otto M. et al., "Step and Repeat UV-Nanoimprint Lithography: Material Issues," Nanoimprint and Nanoimprint Technology Conference, San Francisco, December 11-13, 2002.

Johnson et al., "Advances in Step and Flash Imprint Lithography," SPIE Microlithography Conference, February 23-28, 2003.

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Date: March 11, 2004

Respectfully



Kenneth C. Brooks
Reg. No.' 38393

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Telephone: 512-527-0104
Facsimile: 512-527-0107
patentsrus@earthlink.net

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				Application Number	10/614,716
				Filing Date	07/07/03
				First Named Inventor	Sreenivasan et al.
				Group Art Unit	1732
				Examiner Name	Unassigned
				Attorney Docket Number	P90/MII-51-33V50
Sheet	2	of	5		

[illegible]

Examiner Signature		Date Considered	
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¹Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached.

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				Application Number	10/614,716
				Filing Date	07/07/03
				First Named Inventor	Sreenivasan et al.
				Group Art Unit	1732
				Examiner Name	Unassigned
Sheet	3	of	5	Attorney Docket Number	P90/MII-51-33V50

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	A17	KRUG et al., "Fine Patterning of Thin Sol-Gel Films," Journal of Non-Crystalline Solids, 1992, pp. 447-450, vol. 147 & 148.	
	A18	Krauss et al., "Fabrication of Nanodevices Using Sub-25nm Imprint Lithography," Appl. Phys. Lett 67(21), 3114-3116, 1995	
	A19	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers," Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
	A20	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution," Science, Apr. 5, 1996, pp. 85-87, vol. 272.	
	A21	HAISMA et al., "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication," Journal of Vacuum Science and Technology, Nov/Dec 1996, pp. 4124-4128, vol. B 14(6).	
	A22	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput," Microelectronic Engineering, 1997, pp. 237-240, vol. 35.	
	A23	FELDMAN et al., "Wafer chuck for manification correction in x-ray lithography," American Vacuum Society, 1998, pp. 3476-3479.	
	A24	SCHEER et al., "Problems of the Nanoimprinting Technique for Nanometer Scale Pattern Definition," Journal of Vacuum Science and Technology, Nov/Dec 1998, pp. 3917-3921, vol. B 16(6).	
	A25	COLBURN. et al., "Step and Flash Imprint Lithography: A New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, pp. 379-389, vol. 3676.	
	A26	CHOU et al., "Lithographically-Induced Self Assembly of Periodic Polymer Micropillar Arrays," Journal of Vacuum Science and Technology, Nov/Dec 1999, pp. 3197-3202, vol. B 17(6).	
	A27	RUCHHOEFT et al., "Patterning Curved Surfaces: Template Generation by Ion Beam Proximity Lithography and Relief Transfer by Step and Flash Imprint Lithography," Journal of Vacuum Science and Technology, 1999, pp. 2965-2982, vol. 17.	

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				Group Art Unit	1732
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Sheet	4	of	5	Attorney Docket Number	P90/MII-51-33V50

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	A28	CHOI et al., "Design of Orientation Stages for Step and Flash Imprint Lithography," Precision Engineering, Journal of the International Societies for Precision Engineering and Nanotechnology, 2001, pp. 192-199, vol. 25.	
	A29	CHOI et al., "High Precision Orientation Alignment and Gap Control Stages for Imprint Lithography Processes," U.S. Patent Application 09/698,317. Filed with USPTO on October 27, 2000.	
	A30	SREENIVASAN et al., "High-Resolution Overlay Alignment Methods and Systems for Imprint Lithography," U.S. Patent Application 09/907,512. Filed with USPTO on July 16, 2001.	
	A31	CHOI et al., "Method and System of Automatic Fluid Dispensing for Imprint Lithography Processes," U.S. Patent Application 09/908,455. Filed with USPTO on July 17, 2001.	
	A32	CHOI et al., "Methods for High-Precision Gap and Orientation Sensing Between a Transparent Template and Substrate for Imprint Lithography," U.S. Patent Application 09/920,341. Filed with USPTO on August 1, 2001.	
	A33	BAILEY et al., "Template for Room Temperature Low Pressure Micro- and Nano-Imprint Lithography," U.S. Patent Application 09/976,681. Filed with USPTO on October 12, 2001.	
	A34	VOISIN, "Methods of Manufacturing a Lithography Template," U.S. Patent Application 10/136,188. Filed with USPTO on May 1, 2002.	
	A35	SREENIVASAN et al., "Step and Repeat Imprint Lithography Systems," U.S. Patent Application 10/194,414. Filed with USPTO July 11, 2002.	
	A36	SREENIVASAN et al., "Step and Repeat Imprint Lithography Processes," U.S. Patent Application 10/194,99. Filed with USPTO July 11, 2002.	
	A37	OTTO M. et al., "Step and Repeat UV-Nanoimprint Lithography: Material Issues," Nanoimprint and Nanoprint Technology Conference, San Francisco, December 11-13, 2002.	
	A38	JOHNSON, et al., "Advances in Step and Flash Imprint Lithography," SPIE Microlithography Conference, February 23-28, 2003.	

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				Application Number	10/614,716
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Filing Date	07/07/03
				First Named Inventor	Sreenivasan et al.
				Group Art Unit	1732
				Examiner Name	Unassigned
(use as many sheets as necessary)				Attorney Docket Number	P90/MII-51-33V50
Sheet	5	of	5		

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	A39	CHOI et al., "A Chucking System and Method for Modulating Shapes of Substrates," U.S. Patent Application 10/293,224. Filed with USPTO on November 13, 2002.	
	A40	VOISIN, "Methods of Inspecting A Lithography Template," U.S. Patent Application 10/293,919. Filed with USPTO on November 13, 2002	
	A41	CHOI et al., "A Method For Modulating Shapes of Substrates," U.S. Patent Application 10/316,963. Filed with USPTO on December 11, 2002.	
	A42	NIMMAKAYALA et al., "Magnification Correction Employing Out-of-Plane Distortion of a Substrate," U.S. Patent Application 10/735,110. Filed with USPTO on December 12, 2003.	

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